10-15-04

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No	10/664,744
	September 18, 2003
	Michael T. Andreas
Assignee	Micron Technology, Inc.
Examiner	Fernando L. Toledo
Attorney's Docket No	MI22-2711
	onductor Substrate, Post-CMP Cleaning
Process, and Method of Cleaning	Residue from Registration Alignment
Markings (As Amended)	

RESPONSE TO SEPTEMBER 23, 2004 OFFICE ACTION

To:

Mail Stop Amendment

Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

VIA EXPRESS MAIL

From:

Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)

Wells St. John P.S.

601 West First Avenue, Suite 1300

Spokane, WA 99201-3828

Responsive to the Office Action dated September 23, 2004, Applicant amends and remarks as follows:

<u>AMENDMENTS</u>

In the Title

Please replace the title with:

--Method of Polishing a Semiconductor Substrate, Post-CMP Cleaning Process, and Method of Cleaning Residue from Registration Alignment Markings--.